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(54) LIQUID APPLICATION TYPE AQUEOUS-PROCESSABLE PHOTORESIST COMPOSITION

(57)Abstract:

PURPOSE: To obtain the photoresist having high sensitivity and high resolution by using a (tertiary-butyl methacrylate)/(methyl methacrylate)/(methacrylic acid) polymer binder and an initiator that generates an acid when it is exposed to radiation, as components of the composition.

CONSTITUTION: In this composition, the film-forming polymer binder used is an acrylic polymer that has acid-convertible side chains and is capable of forming a photoresist by allowing it to react with a selected luminescent agent through chemical-sensitizing reaction. Polymer chains of the polymer binder consist of a first monomer that provides a polymer main chain with the acid-sensitive side chain groups, a second monomer that is selected from alkyl methacrylates, alkyl acrylates and combinations of them, and a third monomer that is selected from acryl-based carboxylic acids and methacryl-based carboxylic acids.

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